

SiC Discussion

Thomas Bergauer (HEPHY-OEAW Vienna)

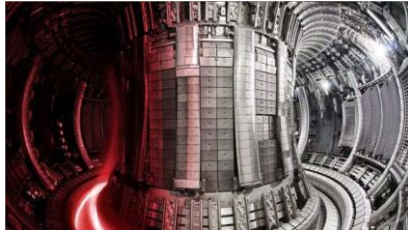
17 November 2023

Silicon Carbide Detectors

- Wide bandgap semiconductor (3.26 eV) : Low leakage currents, insensitivity to visible light
- Renewed interest: High-quality wafers from power electronics industry
- + High breakdown field and saturation velocity: timing applications
- + Potentially higher radiation hardness (displacement energy), no cooling is needed after irradiation
- Higher ionization energy (~30% less signal per μm) [1]
- Limitations in wafer thickness and resistivity



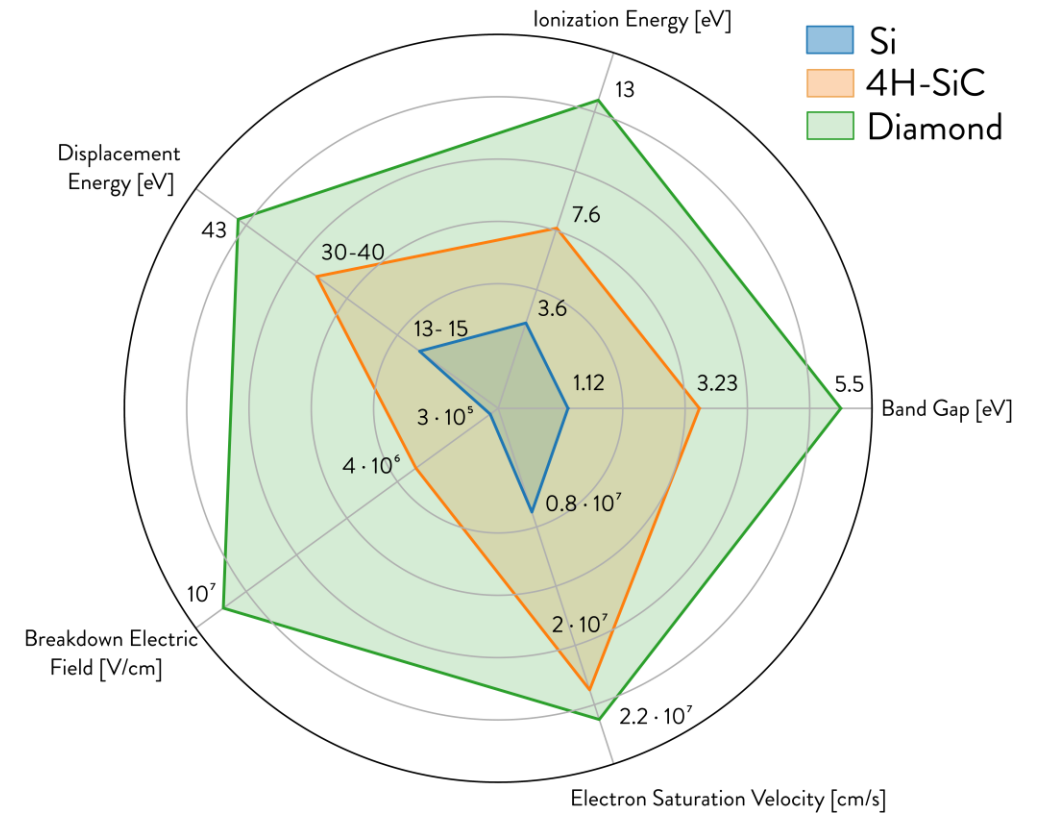
Dosimetry:
 μDOS , FLASH



Space, harsh
environments (fusion)




Beam monitoring, radiation
hard large area detectors



Advantages and disadvantages of 4H-SiC compared to Si

SiC Session

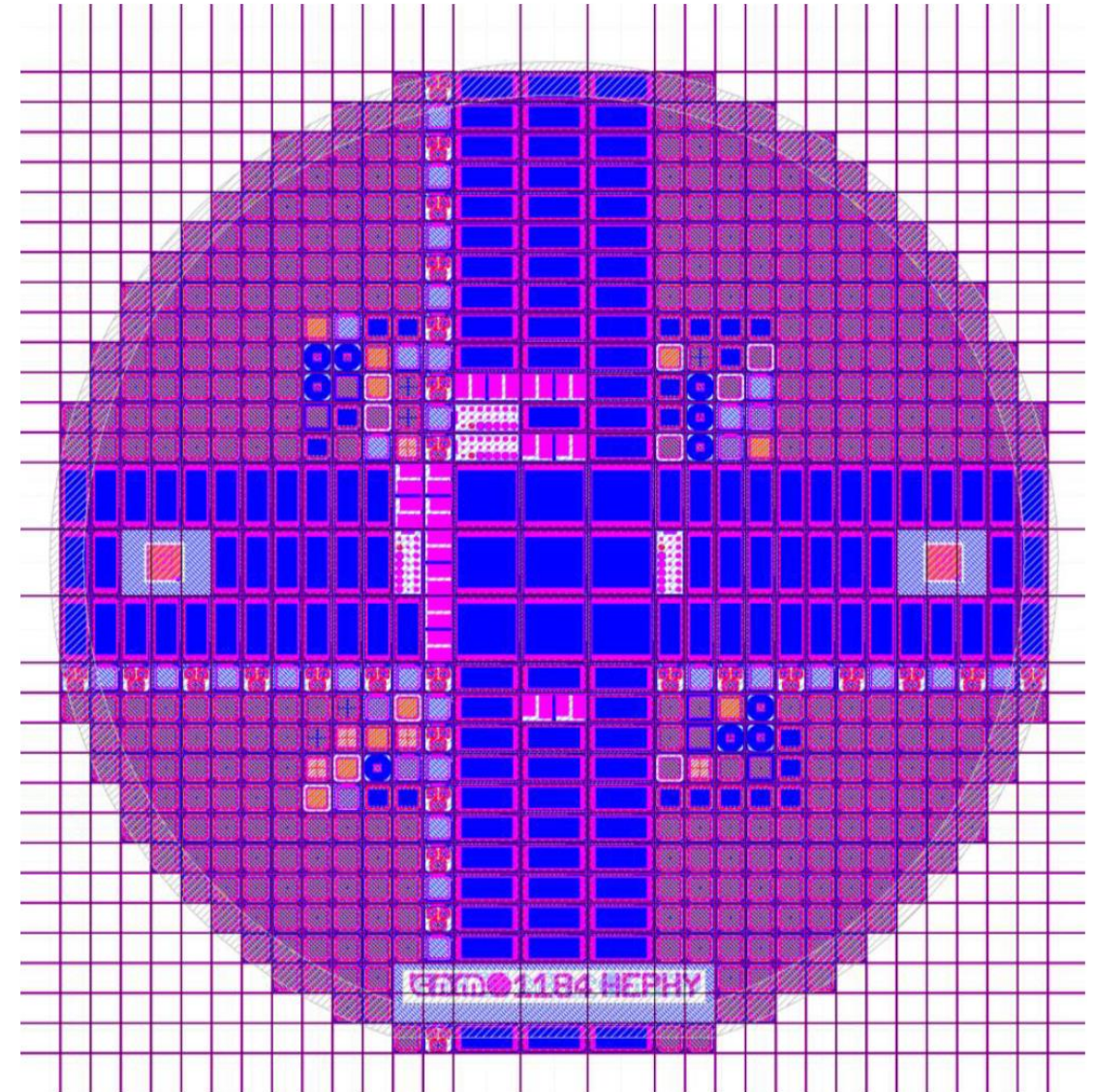
09:00	Four-quadrant Si and SiC Photodiodes for Beam Position and Monitor Applications <i>6/2-024 - BE Auditorium Meyrin, CERN</i>	<i>Dr Joan Marc Rafi</i> 09:00 - 09:20
	Thermal Annealing of Electron, Neutron and Proton Irradiation Effects on SiC Radiation Detectors <i>6/2-024 - BE Auditorium Meyrin, CERN</i>	<i>Dr Joan Marc Rafi</i> 09:20 - 09:40
	Defect Spectroscopy on Proton Irradiated 4H Silicon Carbide Devices <i>6/2-024 - BE Auditorium Meyrin, CERN</i>	<i>Niels Sorgenfrei</i>  09:40 - 10:00
10:00	TCAD simulation of 4H silicon carbide LGADs <i>6/2-024 - BE Auditorium Meyrin, CERN</i>	<i>Philipp Gaggl</i> 10:00 - 10:20
	Coffee break <i>6/2-024 - BE Auditorium Meyrin, CERN</i>	10:20 - 10:50
11:00	Charge Collection Study of SiC-LGAD - SICAR1 <i>6/2-024 - BE Auditorium Meyrin, CERN</i>	<i>Xin Shi</i> 10:50 - 11:10
	Discussion: SiC <i>6/2-024 - BE Auditorium Meyrin, CERN</i>	<i>Thomas Bergauer</i> 11:10 - 11:30

RD50 common project

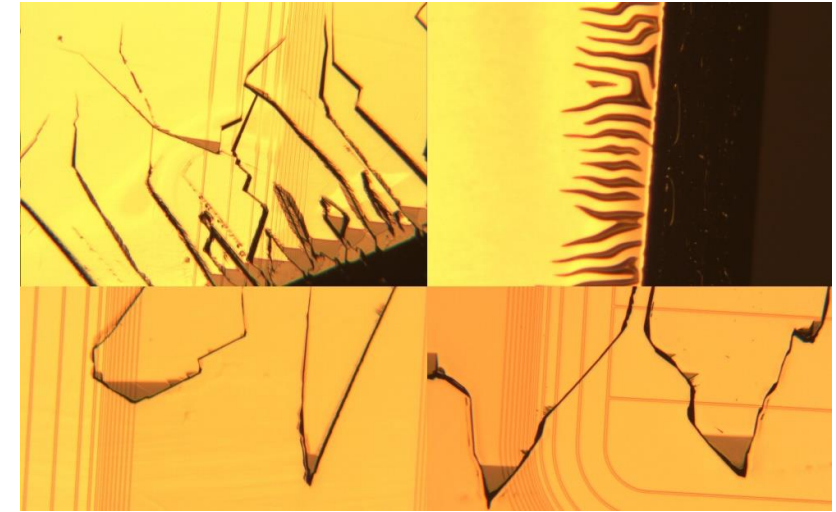
- RD50 project “SiC-LGAD” (RD50-2023-01) approved in March 2023
- Institutes: **HEPHY**, CNM, CERN, Perugia, Santander, NIKHEF
- RD50 fund requested : 30k€ , Total project cost: 110k€

Activity	Institute	Year 1				Year 2				Year 3			
		Q1	Q2	Q3	Q4	Q1	Q2	Q3	Q4	Q1	Q2	Q3	Q4
<i>TCAD simulations</i>	<i>HEPHY, CNM</i>	Planar			LGAD run1			LGAD run2					
<i>Wafer layout</i>	<i>HEPHY, CNM</i>												
<i>Production</i>	<i>CNM</i>												
<i>IV, CV characterization</i>	<i>HEPHY, CNM, Perugia, NIKHEF</i>												
<i>UV-TCT Measurements</i>	<i>HEPHY, CNM</i>												
<i>TPA-TCT Measurements</i>	<i>Santander</i>												
<i>Alibava</i>	<i>CERN</i>												
<i>Neutron Irradiations</i>	<i>HEPHY</i>												
<i>X-Ray irradiations</i>	<i>Perugia</i>												

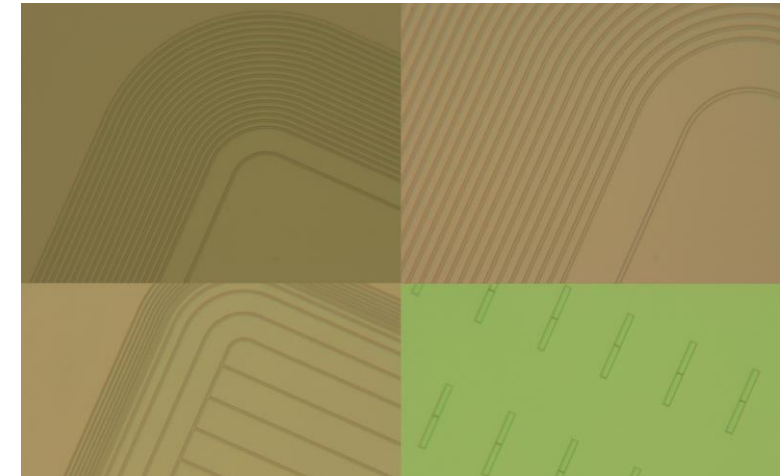
- 4H-SiC wafers in collaboration with CNM
- 3 x 50 μm & 2 x 100 μm epi, 6''
- Design at HEPHY, processing at CNM
- Structures:
 - Pad & strip detectors, resistive detectors
 - Diodes for edge-TCT
 - Pixel array
 - MOSCAPs (various forms and sizes)
 - MOSFETs (various forms and sizes)
 - Gate controlled diodes
 - Test structures (van der Pauw, Kelvin-bridge, ...)



- Completed: 25 / 58 stages
 - Photolithography P-DIFF
 - Ion Implantation: large delay accumulated for the implantation, by IBS (external company)
 - Thermal Oxidation
 - Dry Etching
 - Oxide Deposition
- To do:
 - Windows opening
 - Metallization
 - Passivation
- **Completion expected mid-February 2024**



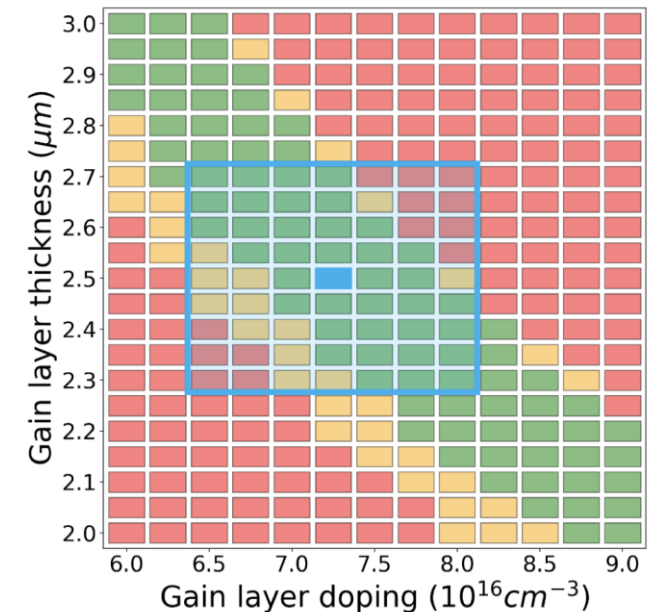
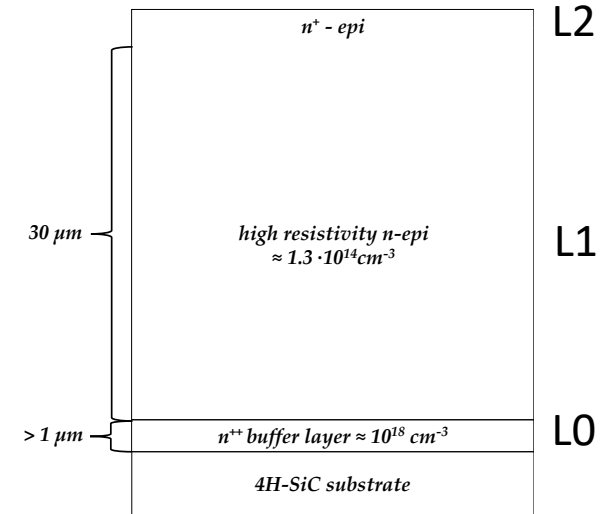
Defects appeared after ion implantation and activation on all the wafers. They are mainly localized at the edge of the wafers.



Status of the wafers

Wafers for SiC-LGAD

- Simulations results in Vienna show that gain can be reached by one single gain layer from top surface down to 2.5 μm (no buried layer)
- Offer from Coherent (II-VI) for 150 mm SiC Epi-Wafer with additional epi layer doping L2:
 - L0=Coherent standard buffer $n \geq 1\text{e}18/\text{cm}^3$,
 - L1= 30 μm $n = 1\text{-}3\text{e}14/\text{cm}^3$,
 - L2= 2.5 $\mu\text{m} \pm 10\%$ $n = 7\text{e}16\text{-}8\text{e}16/\text{cm}^3$.
 - Volume: 5-10 pcs., Price: USD 3.850/pcs, estimated lead-time: ~16-20 weeks
- Target a doping range 7-8e16/cm³ for L2 with stepwise concentration approximation and provide CnCV measurement data. Meeting exact values as specified by you cannot be guaranteed. Epi is done on best effort terms.
- They do not have statistics for 2-3 μm . 10 μm target tolerances are: Thickness deviation $\pm 6\%$ mean, uniformity 4% sigma/mean. N 1e16/cm³ doping deviation $\pm 12\%$ mean, uniformity 10% sigma/mean.



Summary

- SiC Planar Run
 - Ongoing
 - Estimated finish February 2024
- SiC LGAD
 - TCAD simulations ongoing
 - Offer exists; not too expensive
 - Unclear if epi gain layer can be doped to the necessary precision
 - TCAD simulations show that gain is only in a very small range

Discussions

RD50 common project SiC-LGAD

Activity cost	cost/piece	pieces	total costs	comment
Bare wafers	5.000,00 €	15	75.000,00 €	5 wafers per run, 3 runs
Mask set	8.000,00 €	2	16.000,00 €	planar + LGAD
Implantation service	3.000,00 €	3	9.000,00 €	three runs
Wafer processing			5.000,00 €	at CNM
SIMS measurements			2.000,00 €	
Irradiations			3.000,00 €	
Total project costs			110.000,00 €	

Funds	cost/piece	pieces	costs	comment
RD50 common fund			30.000,00 €	
CNM			5.000,00 €	in-kind
HEPHY			50.000,00 €	through HEPHY-CNM contract
Perugia			5.000,00 €	
CERN			10.000,00 €	
Santander			5.000,00 €	
NIKHEF			5.000,00 €	
Total income			110.000,00 €	

